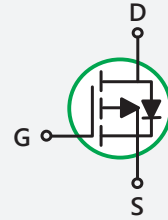
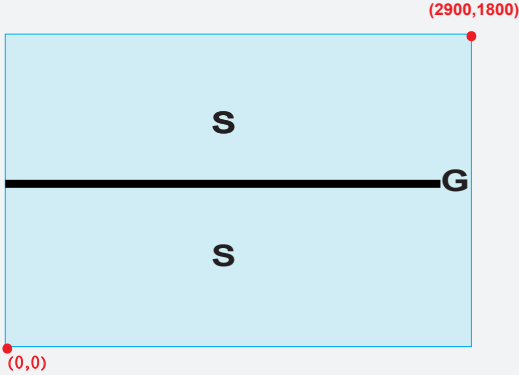


### -100V P Channel Enhancement MOSFET Wafer Datasheet

## FEATURES

- P-Channel, -100V
- $R_{ds(ON)} = 50m\Omega$  (Typ.) @  $V_{GS} = -10V$
- Exceptional on-resistance and maximum DC current capability  
high density cell design for extremely low  $R_{DS(ON)}$



Bonding Pad Information	Chip Information	
	Wafer Name	DC6M100P050M7
	Wafer Diameter	6 inches
	Wafer Thickness	7 mils
	Front-side Metallization	Al/Si/Cu (4um)
	Back-side Metallization	Ti/Ni/Ag
	Bonding Type	Gate: 1.5mil Cu x 1 Source: 40x6mil Al Ribbon x 2
	Die Size (without scribe line)	2900um x 1800um
	Scribe Line Width	60um
	Gate Pad Size	300um x 300um
	Gross Die	2.8K ea

## ABSOLUTE MAXIMUM RATINGS ( $T_c = 25^\circ C$ unless otherwise noted)

Parameter	Symbol	Limit	Units
Drain-Source Voltage	$V_{DS}$	-100	V
Gate-Source Voltage	$V_{GS}$	$\pm 20$	V
Operating Junction and Storage Temperature Range	$T_J, T_{STG}$	-55 to 150	$^\circ C$

## ELECTRICAL CHARACTERISTICS ( $T_c = 25^\circ C$ unless otherwise noted)

Parameter	Symbol	Test Conditions	Min	Typ	Max	Units
Drain-Source Breakdown Voltage	$BV_{DSS}$	$V_{GS} = 0V, I_D = -250\mu A$	-100			V
Zero Gate Voltage Drain Current	$I_{DSS}$	$V_{DS} = -80V, V_{GS} = 0V$			-1	$\mu A$
Gate-Body Leakage Current	$I_{GSS}$	$V_{GS} = \pm 20V, V_{DS} = 0V$			$\pm 100$	nA
Gate Threshold Voltage	$V_{GS(th)}$	$V_{DS} = V_{GS}, I_D = -250\mu A$	-1.0	-1.9	-2.5	V
Drain-Source On-State Resistance	$R_{DS(ON)}$	$V_{GS} = -10V, I_D = -1A$		50	62	m ohm
		$V_{GS} = -4.5V, I_D = -1A$		54	68	m ohm

### Notes:

1. Pulse Test: Pulse Width  $\leq 300\mu s$ , Duty Cycle  $\leq 2\%$ .
2.  $R_{DS(ON)}$  calculated by TO-220 Package Type.